

XP002901448

(C) WPI / DERWENT

- AN - 1982-09501E [05]
PR - SU19792788379 19790504
TI - Formation of gold-like decorative coatings - by depositing thin layer of titanium, tantalum, niobium, tungsten or silicon and electrolytically oxidising
IW - FORMATION GOLD DECORATE COATING DEPOSIT THIN LAYER
TITANIUM TANTALUM NIOBIUM TUNGSTEN SILICON ELECTROLYTIC OXIDATION
PA - (EDUC-R) EDUC ESTAB DES
PN - SU823331 B 19810423 DW198205 003pp
IC - C03C17/24
AB - SU-823331 Decorative gold coatings are deposited on porcelain, ceramic, glass, cermet, enamelled etc. surfaces by: depositing a layer of Ti, Ta, Nb, W or Si; and electrolytically oxidising the deposit in a 0.01-0.1 M salt or acid soln. at a voltage of 30-50 V to form an oxidised layer of thickness 800-1550 Angstrom. The resulting coating has high wear resistance, a bright gold colour and good stability towards acids, alkalis heat etc.
- The adhesion of the coating to the substrate may be enhanced by an intermediate layer formed by the cathodic sputtering of a 150-300 Angstrom layer of a mixt. of the above metal and its oxide. (3pp)